ABSTRACT OF THE DISCLOSURE

IMPRINT METHOD, MOLD, IMPRINT APPARATUS AND ARTICLE MANUFACTURING METHOD

An imprint method of forming a pattern in an imprint material arranged on each of a first region on a substrate and a second region including an overlap region overlapping an edge of the first region, including forming, in the imprint material on the first region, a first pattern including a main pattern and a first portion formed on an overlay pattern formed in the overlap region, and forming, in the imprint material on the second region, a second pattern including a main pattern and a second portion covering the first portion of the first pattern, wherein in the forming the second pattern, the second pattern is formed such that a film thickness of a pattern formed in the overlap region is greater than a film thickness of the main pattern of the second pattern.

(Figure 5)